

Supplementary Information

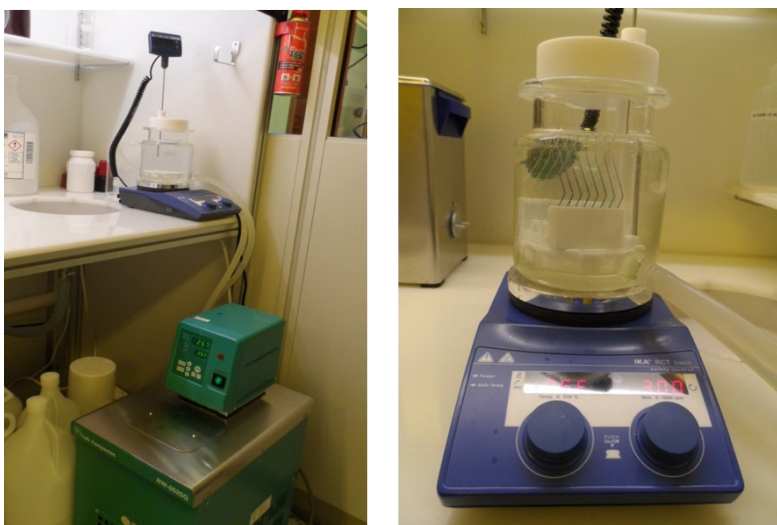


Fig. S1 Photos of the experimental setup for precise develop temperature control. Develop solution was stirred with a magnetic spin bar rotating at 300 rpm.

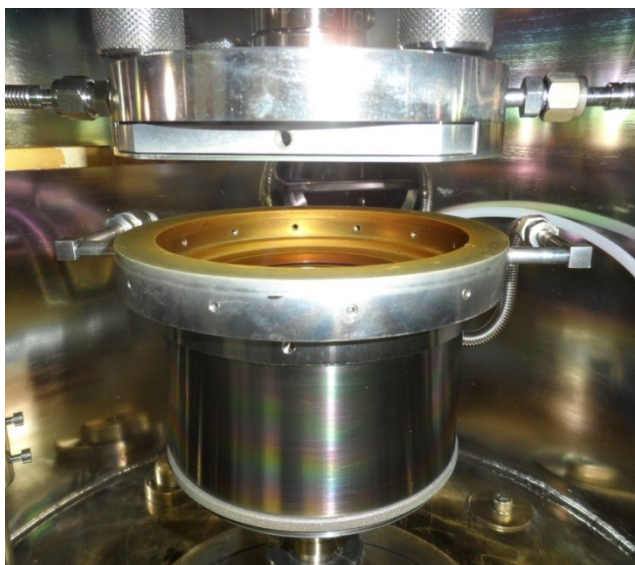


Fig. S2 Photo of the gas delivery unit mounted on the sputter gun for uniform supply.

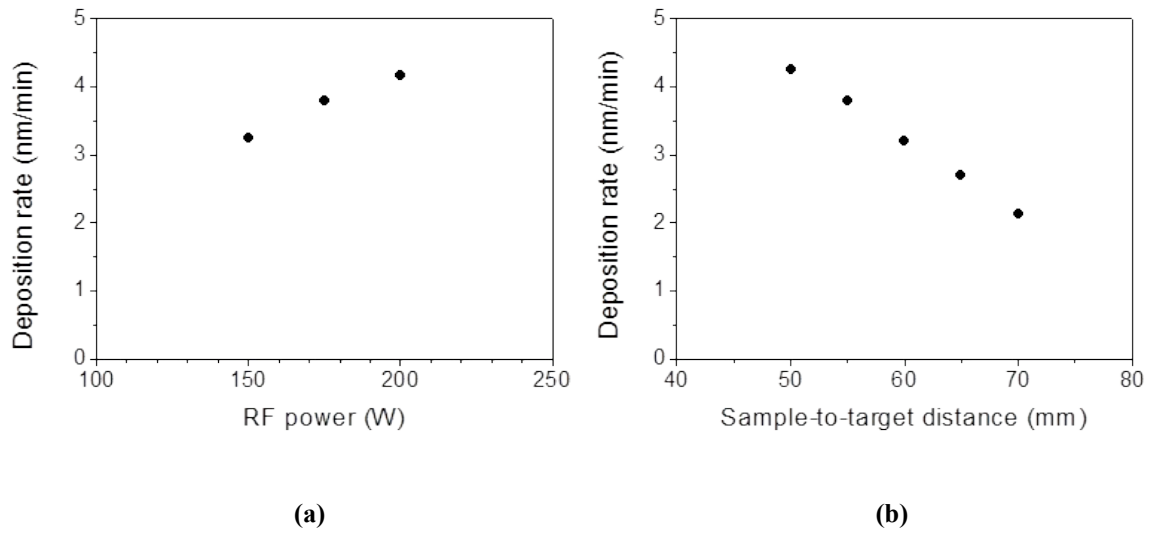


Fig. S3 Dependence of the deposition rate on (a) RF power and (b) sample-to-target distance for sputter system used in this work.